

# INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Attorney Docket Number	5437-60780-01
Application Number	09/921,993
Filing Date	August 2, 2001
First Named Inventor	Chambless
Art Unit	2129
Examiner Name	Lut Wong

## U.S. PATENT DOCUMENTS

Copies of U.S. Patent documents do not need to be provided, unless requested by the Patent and Trademark Office. For patents, provide the patent number and the issue date. For published U.S. applications, provide the publication number and the publication date. For unpublished pending patent applications, provide the application number and the filing date and submit a copy.

Examiner's Initials*	Cite No. (optional)	Number	Date	Name of Applicant or Patentee
		5,325,862	07-1994	Lewis et al.
		6,405,159	06-2002	Bushey et al.
		6,795,799	09-2004	Deb et al.
		6,853,966	02-2005	Bushey et al.
		7,356,484	04-2008	Benjamin et al.

## FOREIGN PATENT DOCUMENTS

Examiner's Initials*	Cite No. (optional)	Country	Number	Publication Date	Name of Applicant or Patentee

## OTHER DOCUMENTS

Examiner's Initials*	Cite No. (optional)	
		Dimpsey, et al., "A Measurement-Based Model to Predict the Performance Impact of System Modifications: A Case Study," <i>IEEE Transactions on Parallel and Distributed Systems</i> , Vol. 6, No. 1, 1995, pp. 28-40, 13 pages.
		Kulonda, Dennis J., "Reengineering Training for Performance Improvement," <i>Portland International Conference on Technology and Innovation Management. PICMET '99</i> , Vol. 1, July 25-29, 1999, pp. 333-334, 2 pages.
		Martin et al., "Using a Conceptually-Based Predictor of Tenure to Select Employees," <i>Journal of Business and Psychology</i> , Vol. 13, No. 2, 1998, pp. 233-243, 11 pages.
		Tokunaga, et al., "Career Progression in a Fortune 500 Company: Examination of the "Glass Ceiling," <i>IEEE Transactions on Engineering Management</i> , Vol. 43, No. 3, 1996, pp. 262-272, 11 pages.

EXAMINER  
SIGNATURE:

DATE  
CONSIDERED:

\* Examiner: Initial if reference considered, whether or not in conformance with MPEP 609. Draw line through cite if not in conformance and not considered. Include copy of this form with next communication to applicant.